

SUMMARY OF INTERVIEW

Attendees, Date and Type of Interview

The interview was conducted by telephone on February 23, 2008, and was attended by Examiner Kelly Stouffer and Applicant's representative, Andrew N. Merickel.

Exhibits and/or Demonstrations

None.

Identification of Claims Discussed

Claim 1 and dependents.

Identification of Prior Art Discussed

Dillon et al. (Surface Science 322(1995) 230-242);

Penneck et al. (U.S. Patent No. 4,985,313).

Proposed Amendments

None.

Principal Arguments and Other Matters

The teachings of the cited references were discussed, along with the particular requirements of ALD processes and the implications of the significant differences between the contexts of the two references. In particular, the lack of teaching of deposition of more than one monolayer of aluminum oxide in Dillon was discussed.

Results of Interview

Applicant agreed to submit a response to the office action consistent with what was discussed in the interview.